

Novel Platinum Precursors for Focused Electron Beam Induced Deposition: $\text{PtCl}_2(\text{CO})_2$ and $\text{PtBr}_2(\text{CO})_2$

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Focused electron beam induced deposition (FEBID) is a single-step gas-assisted additive lithography technique. It provides high spatial resolution fabrication of 3D structures from a precursor gas introduced into a regular scanning electron microscope (SEM). Often, the deposited structures contain unwanted fragments of the precursor molecules for which a solution may be found in the design of novel precursors that decompose into nicer fragments upon electron irradiation. Two new platinum precursors, $\text{PtCl}_2(\text{CO})_2$ and $\text{PtBr}_2(\text{CO})_2$ were synthesized and tested using a standard FEBID process in an SEM. Deposits from both precursors were compared to deposits fabricated from the commonly used MeCpPtMe_3 precursor, and also to deposits made in an ultra-high vacuum (UHV) environment^{1,2}. From both precursors deposits can be grown in SEM, a first promising step for FEBID precursors (fig. 1)³. The growth rates were determined, revealing that $\text{PtBr}_2(\text{CO})_2$ features a lower growth rate ($\sim 0.0035 \text{ nm}^3/\text{e}^-$) than the other two precursors. The growth rate of $\text{PtCl}_2(\text{CO})_2$ ($\sim 0.045 \text{ nm}^3/\text{e}^-$) can be larger than for MeCpPtMe_3 ($\sim 0.020 \text{ nm}^3/\text{e}^-$) depending on the balance between electron flux and precursor flux. The composition, as determined by energy dispersive X-ray (EDX) analysis, of deposits from $\text{PtCl}_2(\text{CO})_2$ ¹ and $\text{PtBr}_2(\text{CO})_2$ made in UHV, consisted of platinum and halogen only, with a stoichiometry of PtX_2 (X=Cl, Br). Surprisingly, deposits made in the SEM contained 50-60 at% carbon, 10-20 at% platinum, 7-10 at% oxygen and about 7 at% halogen. The high carbon content may find its origin in the CO-content in the precursor combined with the presence of hydrocarbons and water in the SEM. Summarizing, $\text{PtCl}_2(\text{CO})_2$ and $\text{PtBr}_2(\text{CO})_2$ can be successfully used in FEBID, but the reasons why the deposit composition is influenced by the deposition conditions still need to be unraveled.

¹ J. Spencer, Y-C. Wu, L. McElwee-White, and D.H. Fairbrother, *Journal of the American Chemical Society* 138, 9172-9182 (2016).

² J. A. Spencer, M. Barclay, M.J. Gallagher, R. Winkler, I. Unlu, Y.-C. Wu, H. Plank, L. McElwee-White, D.H. Fairbrother, *Beilstein J. Nanotechnol.* 8, 2410–2424 (2017).

³ Mahgoub, A.; Lu, H.; Thorman, R. M.; Preradovic, K.; Jurca, T.; McElwee-White, L.; Fairbrother, H.; Hagen, C. W. *Beilstein J. Nanotechnol.* 2020, 11, 1789–1800.
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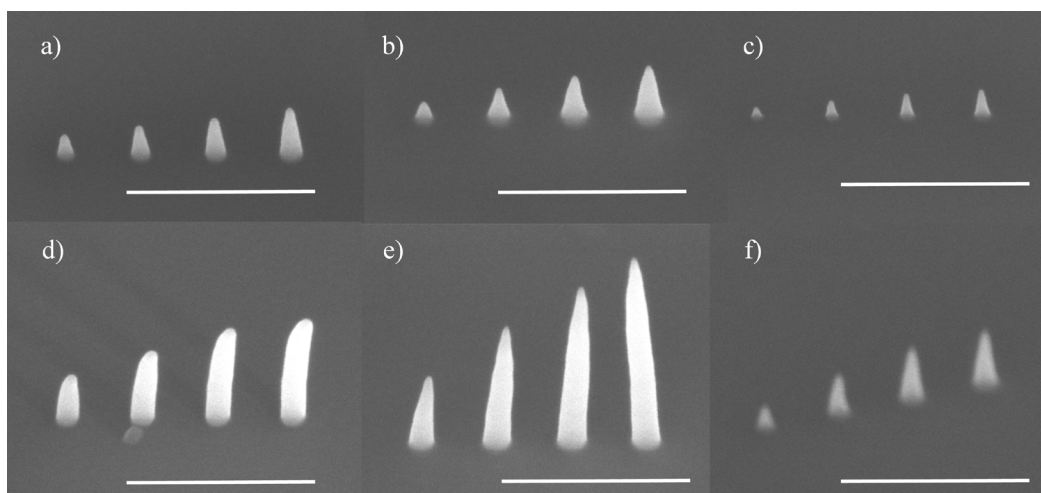


Figure 1: Comparison of pillars grown from all three precursors a) and d) MeCpPtMe₃, b) and e) Pt(CO)₂Cl₂, and c) and f) Pt(CO)₂Br₂. The dwell times for each pillar were 0.5, 1, 1.5 and 2 ms (left to right) and this was repeated for 200 passes. a), b), and c) are deposited at 12 pA. This corresponds to electron doses of 7.5, 15, 22.5, and 30 × 10⁶ electrons. d), e) and f) are deposited at 38 pA, corresponding to electron doses of 24, 47, 71 and 95 × 10⁶ electrons, respectively. The writing strategy consisted of exposure of one pillar for a certain dwell time, then blank the beam for a refresh time, ten times larger than the dwell time, then move to the next pillar. When the first pass over 4 pillars is finished, this is repeated 200 times. All scale bars are 500 nm.